

REMARKS

Favorable reconsideration of this application as presently amended and in light of the following discussion is respectfully requested.

Claims 1, 3, and 4 are pending in the present application. Claims 1, 3, and 4 are amended without adding new matter to rearrange the order of previously recited limitations. As the present amendment only rearranges the order of previously recited limitations and corrects punctuations to improve clarity without any change of claim scope, it does not necessitate the need for a new search and raises no new examination issues. Thus, entry of the present amendment is clearly in order under 37 C.F.R. § 1.116.

In the outstanding Office Action, the drawings were objected to and Claims 1, 3, and 4 were rejected under 35 U.S.C. § 103(a) as unpatentable over Applicants' Admitted Art (AAA) in view of Hong et al. (U.S. Patent No. 6,429,057 B1, herein "Hong").

Regarding the objection to Figures 57-60, those figures are labeled "Prior Art" as suggested in the outstanding Office Action. Accordingly, it is respectfully requested that this objection be withdrawn.

Claims 1, 3, and 4 were rejected under 35 U.S.C. § 103(a) as unpatentable over AAA in view of Hong. That rejection is respectfully traversed.

Independent Claims 1, 3, and 4 have been amended to even more clearly require that "both outer edges of" a part of a "semiconductor pattern" that exists only on a first metallic pattern of a source electrode part in a pixel region must also surround the source electrode as clearly shown in Figures 1, 2(a), and 17, and disclosed in the specification, at page 30, lines 14-21 for example.

Briefly recapitulating, amended independent Claim 1 is directed to a thin film transistor array substrate having an insulating substrate, a first metallic pattern formed on the

insulating substrate, an insulating film provided on the first metallic pattern, a semiconductor pattern provided on the insulating film, and a second metallic pattern provided on the semiconductor pattern. In addition, the second metallic pattern is surrounded by the semiconductor pattern and both outer edges of a part of the semiconductor pattern that exists only on the first metallic pattern at the source electrode part in a pixel region also surrounds the source electrode. Independent Claims 3 and 4 have been amended to recite similar features as Claim 1.

In a non-limiting example, Figure 2(a) shows the first metallic pattern 1, the insulating film 3, the semiconductor pattern 4a, the second metallic pattern 4b, and that the left side part of layer 4a under 6 and over 1 clearly exists only on pattern 1 while it surrounds the source electrode 6.

The outstanding Office Action recognizes at page 3, first full paragraph, that AAA “do not expressly teach the source electrode and the drain electrode are surrounded by the semiconductor layer.” It is further submitted that AAA does not teach or suggest that both outer edges of the part of the semiconductor pattern that is on the first metallic pattern at the source electrode part in a pixel region also surrounds the source electrode.

In an effort to cure the deficiencies of AAA, the rejection turns to Hong. The outstanding Office Action specifically asserts (at page 4, paragraph 5) that Hong shows in Figure 4 “a part of the semiconductor layer 42 surrounding a source electrode 66 exists only on the first metallic pattern 26 at a source electrode part.” However, no outer edges of the semiconductor pattern 42 in Hong that exists only on the first metallic pattern 26 can be said to surround the source electrode 66 as required in Claim 1. Thus, Hong does not cure the above-noted deficiencies of AAA.

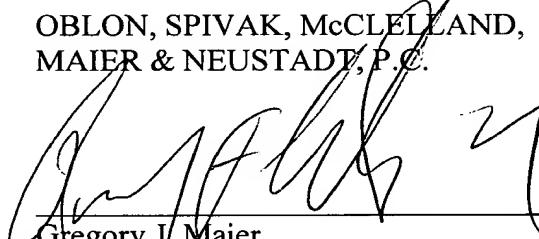
Moreover, the reliance on the Hong teaching of column 1, lines 64-67 clearly relates to using its new methods for manufacturing a TFT array panel and not simply how layer 42 is formed relative to electrodes 65 and 66 as improperly suggested in the paragraph at the bottom of page 3 of the outstanding Office Action. See In re Kotzab, 55 USPQ2d 1313, 1317 (Fed. Cir. 2000) requiring reference statements to be considered in context.

Accordingly, it is respectfully submitted that independent Claims 1, 3, and 4 patentably distinguish over AAA and Hong.

Consequently, in light of the above discussion and in view of the present amendment, the present application is believed to be in condition for allowance and an early and favorable action to that effect is respectfully requested.

Respectfully submitted,

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